

Fig. 1

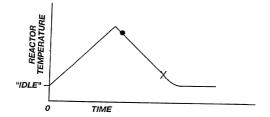


Fig. 3

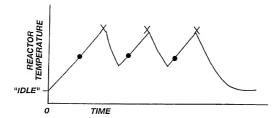


Fig. 2

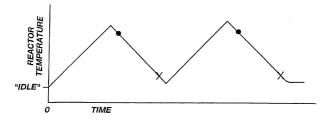


Fig. 6

10047651.011402

TENCOR INSTRUMENTS PROMETRIX UV-1250SE TENCOR PRSE401 ■ Sigma Error
■ Measurement Error
- Below Calculated Mean
+ Above Calculated Mean GOF Error Thick Nitride 1X DBS 240-800 Pyrolytic Si3N4 Silicon 10 mm Polar/49 Site Map 49/49 1st Thickness 1833.47.A 20.5599.A/ 1.121% 1808.59.A 1874.90.A Right /3 05/13/96 00:02:31 11/13/96 20:31:52 Percent 0.00 A 10 %/10 % 6 %/5 % 3 / 3 Process:
Wafer Diameter: 200 mm
Edge Exclusion: 10 mm
Type Pattern: 99/49
Measurement: 1st Thickn Absolute 16.681 Limits:

Mean Target: (
UIL Control: 11
UIL Sigma: 3
Sidv Control: 1
Contour Display: A 2-D Contour Map Std. Deviation: Minimum: Maximum: Cassette/Slot: Processed: Collected: Equipment Lot ID: Water ID: Operator: Shift: Film Stack: Layer 1: Substrate: Range: nterval: Status: Mean:

Fig. 4 (PRIOR ART)

204110" TSOZ4001

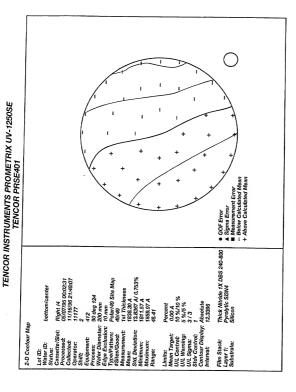


Fig. 5

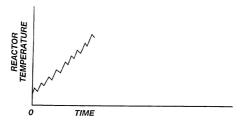


Fig. 7

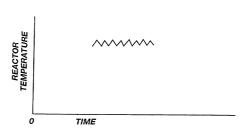


Fig. 8

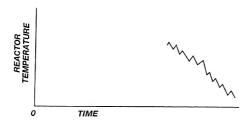


Fig. 9

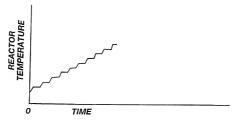


Fig. 7a

ROUNTED TOTAL

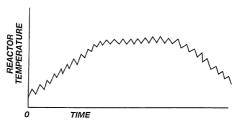


Fig. 10a

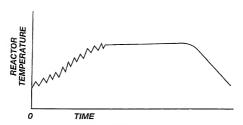


Fig. 10b

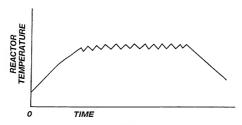


Fig. 10c

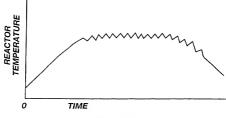


Fig. 10d

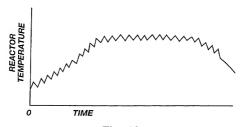


Fig. 10e



Fig. 11

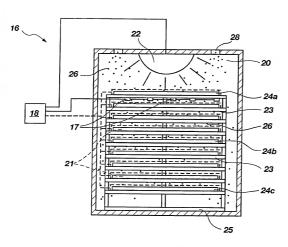


Fig. 12